

## PRESS RELEASE

### Heidelberg Instruments and GenISys Announce Cooperation on Maskless Laser Lithography

**Heidelberg, GERMANY, October 21, 2014** – *Heidelberg Instruments*, a leading supplier of equipment and process solutions for laser lithography related markets and GenISys GmbH, a provider of high-performance software solutions for nanoscale fabrication, today announced a cooperation agreement to combine the Heidelberg Instruments laser lithography tools with the GenISys data-preparation, simulation and process correction software packages of BEAMER™ and LAB™.

Within the cooperation GenISys BEAMER™ has been adapted to support Heidelberg Instruments laser exposure systems with advanced layout data preparation. The 3D simulation software LAB™ has been extended to model the exposure of HIMT laser systems in 3D, enabling a subsequent simulation of the resist process. Both parties have joined forces to market the Heidelberg systems with the GenISys lithography software packages. The combination of advanced lithography equipment and powerful data preparation, simulation and process correction software is a key success factor for cost effective process and device development for the end user.

“The latest sophisticated HIMT maskless laser lithography technology combines high throughput for exposing very large pattern data such as full masks or wafer plus high resolution going from below 0.5µm minimum feature sizes along with providing excellent process control enabling 3D patterning”, said Steffen Diez Member of the Technical Board of Heidelberg Instruments GmbH. “This combination with the GenISys lithography software packages is a key technology enabler as the comprehensive layout modification techniques of BEAMER are optimized for processing of complex and large layout data volumes. The optimal data preparation for the exposure combined with simulation and process correction offer new possibilities for resolution enhancement and grey tone lithography .”

“BEAMER today is the standard software for preparing layout data for electron beam lithography at most nano-fabrication centers worldwide. The capability of using BEAMER and LAB for the Heidelberg systems is enabling the user to push the limits of laser lithography to higher productivity and more demanding applications. This comprehensive software platform combining clever layout data preparation, simulation and correction technologies is essential to optimize exposure results by mitigating process and tool artifacts.” said Nezih Unal, Vice President of GenISys.

#### **About GenISys**

Based in Munich, Germany, with offices in Tokyo, Japan, and Santa Clara, Calif., GenISys GmbH develops, markets and supports flexible, high-performance software solutions for the optimization of microstructure fabrication processes. Addressing the market for e-beam direct-write and optical lithography, GenISys combines deep technical expertise in layout data processing, process modeling, correction and optimization with high-caliber software engineering and a focus on ease of use. GenISys products give researchers, IC and MEMS manufacturers and system suppliers unparalleled efficiency, ease of use and optimal value in research, development and production of new micro-patterning technologies.

For more information visit us at [www.genisys-gmbh.com](http://www.genisys-gmbh.com) .

#### **Contact:**

[info@genisys-gmbh.com](mailto:info@genisys-gmbh.com)  
+49 89 330919 760

#### **About Heidelberg Instruments**

Heidelberg Instruments GmbH,

With an installation base in over 40 countries, Heidelberg Instruments is a world leader in production of high precision maskless lithography systems. These systems are used for direct writing and photomask production by some of the most prestigious universities and industry leaders in the areas of MEMS, BioMEMS, Nano Technology, ASICS, TFT, Plasma Displays, Micro Optics, and many other related applications.

For more information, please visit <http://www.himt.de>.

#### **Contact:**

[sales@himt.de](mailto:sales@himt.de)